

Title (en)  
POSITIVE PHOTORESIST COMPOSITIONS

Publication  
**EP 0200129 B1 19920205 (DE)**

Application  
**EP 86105450 A 19860419**

Priority  
DE 3515693 A 19850502

Abstract (en)  
[origin: EP0200129A2] Scattered radiation and halation effects can be effectively suppressed in positive photoresist coatings, especially when they are applied to highly reflective substrates by adding compounds of the general formula I <IMAGE> where R<1> to R<4> denote, in each case, hydroxyl or C1-6-alkoxy and R<5> to R<10> denote, in each case, hydrogen or C1-6-alkyl, to photoresist compositions with a diazoquinone/novolak base.

IPC 1-7  
**G03F 7/022**; **G03F 7/09**

IPC 8 full level  
**G03F 7/022** (2006.01); **G03F 7/09** (2006.01)

CPC (source: EP)  
**G03F 7/0226** (2013.01); **G03F 7/091** (2013.01)

Cited by  
EP0298393A3; EP0287750A3; US4818658A

Designated contracting state (EPC)  
AT DE FR GB IT NL

DOCDB simple family (publication)  
**EP 0200129 A2 19861105**; **EP 0200129 A3 19871104**; **EP 0200129 B1 19920205**; AT E72488 T1 19920215; DE 3515693 A1 19861106; DE 3683794 D1 19920319

DOCDB simple family (application)  
**EP 86105450 A 19860419**; AT 86105450 T 19860419; DE 3515693 A 19850502; DE 3683794 T 19860419